2nd Announcement and Call for Papers

Photomask Japan 2026

April 8(Wed.) - 10(Fri.), 2026

PACIFICO Yokohama (Annex Hall), Yokohama, Japan

The 32nd Symposium on Photomask and Next Generation Lithography Mask Technology

Photo credit: Yokohama Visitors Guide

Organized by

PMJ PhotoMask Japan

SPIE.

Co-organized by

SPIE. BACUS PHOTOMASK TECHNOLOGY GROUP

EMLC

Supported by

明日をひらく都市
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https://smartconf.jp/content/pmj2026

SPIE Proceedings Coordinator
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Symposium Chair: **Prof. Takeo Watanabe, University of Hyogo (Japan)**
Organized by Photomask Japan and SPIE
Co-organized by BACUS and EMLC

Papers are solicited on the following and related topics:

- **Materials for photomasks**
- **Fabrication process steps and equipment for photomasks (developing, etching, cleaning etc.)**
- **Photomask writing tools and technologies including multi-beam EB writer**
- **Tools and technologies for metrology/ inspection/ repair**
- **Technologies and infrastructures for EUVL masks**
- **Technologies and infrastructures for NIL masks**
- **Technologies and infrastructures for FPD masks**
- **EDA, MDP, curvilinear ILT and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and multiple patterning**
- **Photomask-related lithography technologies**
- **NGL mask technologies and their applications: DSA and others**
- **Strategy and business challenges: cost, cycle time and total mask solutions**
- **Patterning technologies for semiconductor and electronic devices**
- **Semiconductor manufacturing technologies**
- **Advanced package, Chiplets**
- **eBeam direct writing and eBeam lithography technologies**
- **Utilizing AI technologies for the efficiency of R&D and HVM**
- **Legacy tools for middle and low-end masks**
- **Photomask and lithography related technologies in academia**

See the next page for more information ↓

PMJ website will begin accepting abstracts: October 1 (Wed.), 2025

Abstract Due Date: November 30 (Sun.), 2025

Manuscript Due Date: March 31 (Tue.), 2026

All abstracts must be registered electronically with the PMJ website at:

https://smartconf.jp/content/pmj2026

The electronic abstract submission system will close on time and late abstracts will not be accepted.

To submit an abstract:

Abstracts must be written and presented in **English**, for more details, see the right column.

All abstracts must be submitted electronically in a **PDF file** via the symposium website. No fax and e-mail submission are accepted.

Abstracts will be published in **Digest of Papers**, which will be distributed to all participants at the symposium.

You will receive your paper registration number in your "My Page". If you do not find it, please contact the Photomask Japan Secretariat.

If electronic submission is not possible then authors are asked to contact the Photomask Japan Secretariat before the abstract due date.

Photomask and Lithography related Technology in Academia

PMJ offers an opportunity for university students or postdoctoral researchers to present their works on mask/lithography technology fields.

Those who wish to present their works are asked to submit an abstract via online in accordance with the guidance of the Abstract Submission page on the website.

Session Scope: Mask technology, lithography technology and applications

Object Presenter: Applicants should be university students or postdoctoral researchers

Registration Fee: Free for presenter

Best Academic Poster Award: Best poster will be selected by voting.

[Extra Prize] "HOYA Best Academic Award"
Prize money: JPY100,000.

All abstracts must contain the following information:

The PMJ abstract template is available on the website, we highly recommend using it.

1. Title of Abstract:

The title of the abstract should be written in Times New Roman, bold, 16pt, centered. Initial letters of each word should be capitalized.

2. Names of All Authors:

Author's name and affiliation spelled out completely in Times New Roman, 12pt, centered. Initial letters of each word must be capitalized. If there are several authors or affiliations, Presenting Author should be listed first and the related numbers should be given using superscripts. Also include the mailing address, and email address.

E.g., Noriaki Nakayamada[1],Tetsuo Harada[2], Yusuke Kawano[3], Daisuke Kenmochi[4]
[1] TSMC (Taiwan), [2] University of Hyogo (Japan), [3] Renesas Electronics Corporation (Japan), [4] HOYA Corporation (Japan),
168, Kehuan Rd., Baoshan Township, Hsinchu County 308-xxxx, Taiwan
E-mail: Noriaki@xxxxx.com

3. Abstract Text and Figures:

Text should be approximately 250 words, not exceeding one A4 page including figures.

4. Keywords:

List maximum of five keywords. Please choose at least one keyword for your abstract.

Notification of Acceptance:

The Photomask Japan Program Committee will review all contributed abstracts. Applicants will be notified of acceptance or rejection by e-mail no later than the end of January 2026.

Note: This information is subject to change without notice. PMJ requests all prospective authors to regularly check the PMJ website for updates.

Abstract Submission Office

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